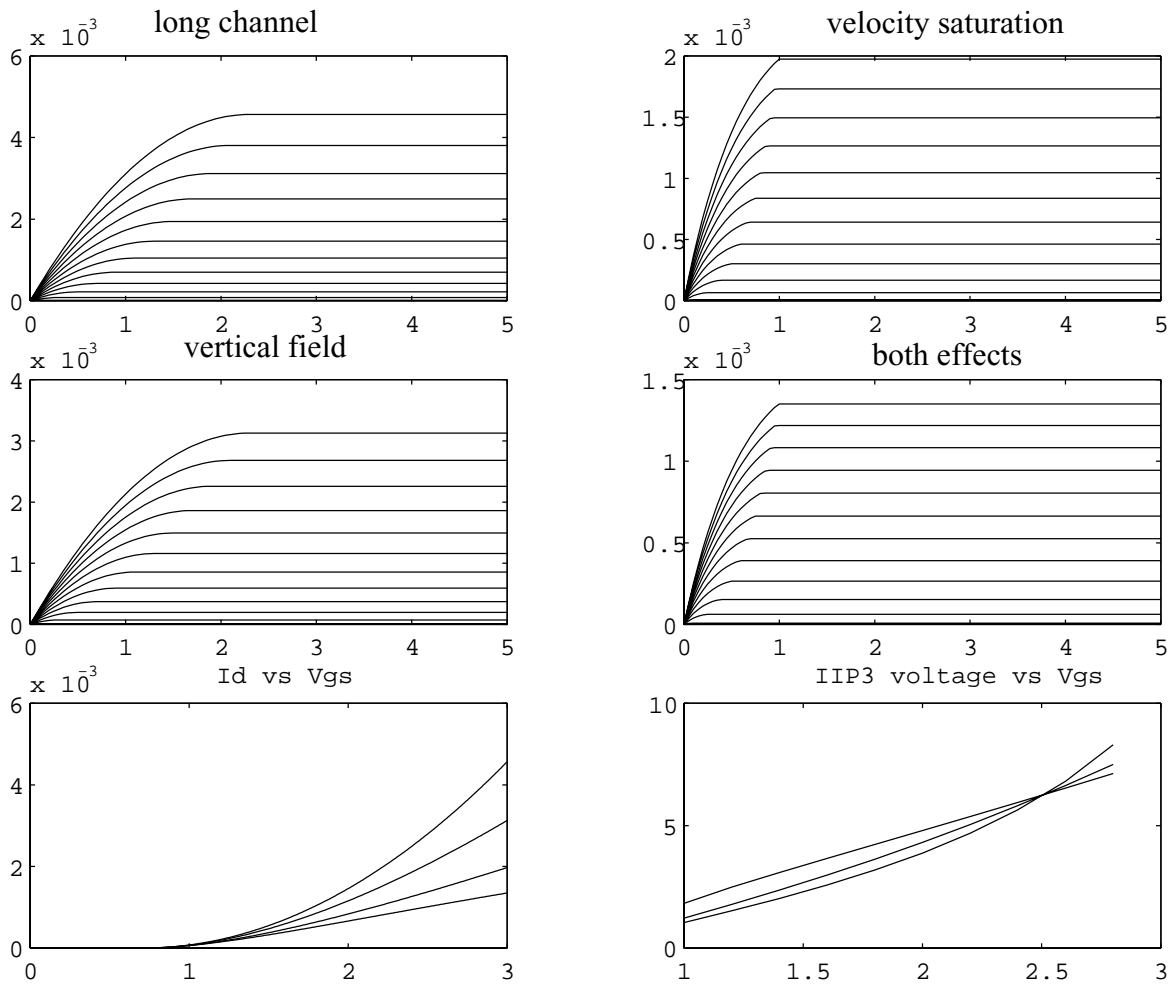


Solutions exercise 2 (components)

1. Problem 3.4

Solved numerically in Matlab.



The two plots in the bottom are extras. They show how I_d and IIP3 vs V_{gs} looks for the four cases. One case is omitted in the IIP3 plot, since in the long channel case IIP3 is infinite.

2. Problem 3.1

$$L_D \approx \frac{2}{3}x_j \quad C_{ov} = L_D W C_{ox} \approx \frac{2}{3}x_j W C_{ox}$$

Assume the transistor to be in saturation:

$$C_{gd} = C_{ov} \quad C_{gs} = \frac{2}{3}C_{gc} + C_{ov} = \frac{2}{3}C_{ox}W(L - 2L_D) + L_D W C_{ox}$$

$$\frac{C_{gd}}{C_{gs}} = \frac{L_D W C_{ox}}{\frac{2}{3}C_{ox}W(L - 2L_D) + L_D W C_{ox}} = \frac{L_D}{\frac{2}{3}L - \frac{1}{3}L_D} = \frac{3L_D}{2L - L_D} = \frac{2x_j}{2L - \frac{2}{3}x_j} = \frac{3x_j}{3L - x_j}$$

The curves can be plotted in Matlab. Some extreme values:

x_j	L	C_{gd}/C_{gs}
250nm	0.5um	60%
50nm	5um	1%
250nm	0.5um	5%
50nm	0.5um	10%

3. Problem 3.3

$$\text{Eq. 3.28 \& 3.29} \Rightarrow I_D = \frac{\mu C_{ox}}{2} \cdot \frac{W}{L} (V_{gs} - V_t)^2 \cdot \frac{LE_{sat}}{(V_{gs} - V_t) + LE_{sat}}$$

$$\begin{aligned} g_m &= \frac{\partial I_D}{\partial V_{gs}} = \frac{\mu C_{ox}}{2} \cdot \frac{W}{L} \cdot LE_{sat} \cdot \frac{2(V_{gs} - V_t)[(V_{gs} - V_t) + LE_{sat}] - (V_{gs} - V_t)^2}{[(V_{gs} - V_t) + LE_{sat}]^2} \\ &= \frac{\mu C_{ox}}{2} \cdot \frac{W}{L} \cdot LE_{sat} \cdot (V_{gs} - V_t) \cdot \frac{2[(V_{gs} - V_t) + LE_{sat}] - (V_{gs} - V_t)}{[(V_{gs} - V_t) + LE_{sat}]^2} \\ &= \frac{\mu C_{ox}}{2} \cdot W E_{sat} \cdot (V_{gs} - V_t) \cdot \frac{(V_{gs} - V_t) + 2LE_{sat}}{[(V_{gs} - V_t) + LE_{sat}]^2} \end{aligned}$$

$$C_{gs} \approx \frac{2}{3}WLC_{ox} \quad (\text{in saturation})$$

$$\begin{aligned} \omega_t &\approx \frac{g_m}{C_{gs}} \approx \frac{3}{2} \frac{1}{WLC_{ox}} \frac{\mu C_{ox}}{2} W E_{sat} \cdot (V_{gs} - V_t) \cdot \frac{(V_{gs} - V_t) + 2LE_{sat}}{[(V_{gs} - V_t) + LE_{sat}]^2} \\ &= \frac{3\mu E_{sat}}{4L} \cdot (V_{gs} - V_t) \cdot \frac{(V_{gs} - V_t) + 2LE_{sat}}{[(V_{gs} - V_t) + LE_{sat}]^2} \end{aligned}$$

To verify the result, check the limits LE_{sat} towards zero and infinity. They must be possible to simplify to the short-channel and long-channel equations.

4. Problem 3.5

$$g_m = \mu C_{ox} \frac{W}{L} (V_{gs} - V_t) \Rightarrow \{(V_{gs} - V_t) = 1V = \text{constant}\} \Rightarrow g_m \sim \mu \sim T^{-\frac{3}{2}}$$

$$\frac{g_{m400K}}{g_{m300K}} = \left(\frac{400}{300}\right)^{-\frac{3}{2}} = 0.65$$

Result: g_m decreases by 35%

5. Problem 3.8

The short-channel effects will affect the matching if the length of the transistors are different.

6. Inductor design

Requirements: $L=5\text{nH}$, $f_s > 4.8\text{GHz}$

Process: $t_{\text{met}}=3\mu\text{m}$, $t_{\text{ox}}=4\mu\text{m}$

Goal: maximize Q

Since the substrate losses is neglected, go for maximum dimensions to minimize the series resistance. The dimensions are limited by the f_s requirement.

$$f_s = \frac{1}{2\pi\sqrt{L \cdot C_{ox}/2}} \Rightarrow C_{ox} = \frac{2}{4\pi^2 f_s^2 L} = 440\text{fF}$$

$$C_{ox} = \frac{\text{Area}}{t_{ox}} \cdot \epsilon \Rightarrow \text{Area} = \frac{C_{ox} \cdot t_{ox}}{\epsilon} = 51000(\mu\text{m})^2$$

A track width W of $16\mu\text{m}$ is first tested. The maximum length then becomes 3.19mm if the maximum area is not to be exceeded. Test four turns and a spacing of $2\mu\text{m}$.

$$a = \frac{\text{length}}{\#\text{turns} \cdot 8} = 100\mu\text{m} \quad L = \frac{37.5 \cdot \mu_0 \cdot \#\text{turns}^2 \cdot a^2}{22r - 14a} = 5.4\text{nH}$$

Test $W=20\mu\text{m}$, $\text{length}=2.55\text{mm}$, $\#\text{turns}=5$, and $\text{spacing}=2\mu\text{m} \Rightarrow L=5.4\text{nH}$ OK.

This is possible to build (innermost turn has enough radius). It has a lower resistance than the first solution thanks to its larger width and shorter length, so we choose this one.

Lets now calculate the Q:

$$\delta = \sqrt{\frac{2}{\omega\mu\sigma}} = 1.7\mu\text{m} \quad R_s = \frac{\text{length} \cdot \rho}{W\delta(1 - e^{-t_{\text{met}}/\delta})} = \frac{2.55\text{mm} \cdot 2.7 \cdot 10^{-8}\Omega\text{m}}{20\mu\text{m} \cdot 1.7\mu\text{m} \cdot (1 - e^{-3/1.7})} = 2.44\Omega$$

$$Q = \frac{\omega L}{R_s} = 30.9$$

The Q is very high, since the substrate losses are neglected.

7. Problem 2.1

$$C_{corr} = \epsilon \cdot \frac{\pi(R+H)^2}{H} = \epsilon \cdot \left(\frac{\pi R^2}{H} + 2\pi R \right) = C_{uncorr} + \epsilon \cdot 2\pi R$$

\uparrow correction term

$$\frac{C_{corr}}{C_{uncorr}} = \frac{\frac{\pi R^2}{H} + 2\pi R}{\frac{\pi R^2}{H}} = 1 + 2\frac{H}{R} = 1 + 4\frac{H}{D}$$

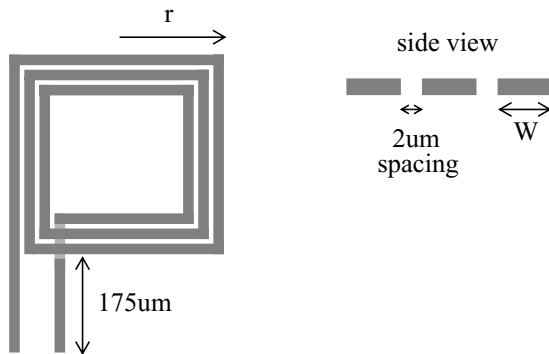
where H is oxide thickness, R is the radius and D is the diameter.

H/D	C_{corr}/C_{uncorr}	from table 2.5
0.005	1.02	1.023
0.01	1.04	1.042
0.025	1.1	1.094
0.05	1.2	1.167
0.1	1.4	1.286

\downarrow The errors become substantial

8. Problem 2.2

a.



first test: $r=120\mu\text{m}$

$$w=5\mu\text{m} \Rightarrow a=85\mu\text{m}$$

$$n=11$$

$$L = \frac{37.5 \cdot \mu_0 \cdot n^2 \cdot a^2}{22r - 14a} = 28\text{nH}$$

Too high. Try smaller r and n and fine tune:

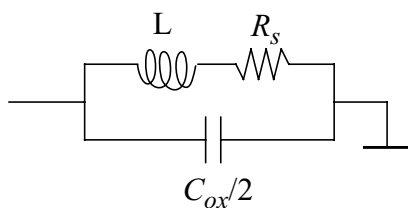
$$r=86\mu\text{m}$$

$$w=5\mu\text{m} \quad a=65\mu\text{m}$$

$$n=7 \quad L=10\text{nH}$$

b.

model:

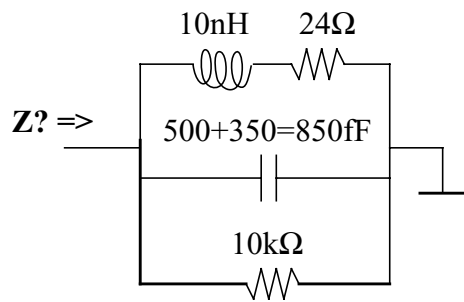


$$\delta = \sqrt{\frac{2}{\omega \mu_0 \sigma}} = 2\mu\text{m}$$

$$R_s = \frac{l}{w\sigma\delta(1 - e^{-l/\delta})} = \frac{8na + 350\mu\text{m}}{w\sigma\delta(1 - e^{-l/\delta})} = 25\Omega$$

$$C_{ox} = \frac{wl\epsilon_{ox}}{t_{ox}} = 700\text{fF}$$

c.



$$f_0 = \frac{1}{2\pi\sqrt{LC}} = 1.73 \text{ GHz}$$

$$Q_L = \frac{\omega_0 L}{R_s} = 4.35$$

$$R_{pL} = R_s(Q_L^2 + 1) = 500 \Omega$$

$$Z|_{f_0} = R_{ptot} = \frac{R_{pL} \cdot 10\text{k}\Omega}{R_{pL} + 10\text{k}\Omega} = 475 \Omega$$

With more metal layers, a higher Q and/or lower parasitic capacitance can be achieved.

9. Problem 2.5

Given:

$$i_D = I_s \cdot e^{v_i/v_T} \quad v_T = 25\text{mV} \quad \& \quad v_j = 0.5\text{V} \Rightarrow i_D = 1\text{mA}$$

$$C_{j0} = 2\text{pF} \quad n = \frac{1}{2} \quad \phi = 0.8\text{V}$$

a. Calculate the incremental resistance at $V_j = 0.5\text{V}$

$$g_d = \frac{\partial i_D}{\partial v_i} = \frac{I_s}{v_T} \cdot e^{v_j/v_T} = \frac{i_D}{v_T}$$

$$\text{at } 0.5\text{V: } g_d = \frac{1\text{mA}}{25\text{mV}} = 0.04\text{S} \Rightarrow r_d = \frac{1}{g_d} = \frac{1}{0.04} = 25\Omega$$

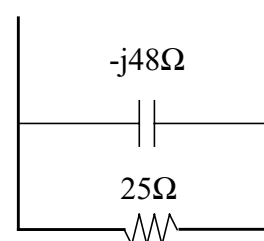
b. Calculate the capacitance at $V_j = 0.5\text{V}$

$$C_j = \frac{C_{j0}}{(1 - V_j/\phi)^n} = \frac{2\text{pF}}{\sqrt{1 - 0.5/0.8}} = 3.3\text{pF}$$

c. Calculate reactance at 1GHz ($V_j=0.5\text{V}$)

$$\frac{1}{j\omega C} = \frac{1}{j \cdot 2\pi \cdot 1 \cdot 10^9 \cdot 3.3 \cdot 10^{-12}} = -j48\Omega$$

The varactors appears mainly resistive at 1GHz (see figure to the right)



10. Problem 2.9

$$R_0 = 10 \text{ k}\Omega \quad R_{square} = 100\Omega$$

a. $W = W_0 \pm 0.2\mu\text{m} \quad R = R_0 \pm 5\%$

$$R = R_0 \cdot \frac{W_0}{W} \Rightarrow 0.95 < \frac{R}{R_0} = \frac{W_0}{W} > 1.05 \Rightarrow \frac{W_0}{W_0 + 0.2\mu\text{m}} > 0.95, \frac{W_0}{W_0 - 0.2\mu\text{m}} < 1.05$$

$$\Rightarrow W_0 \geq 4.2\mu\text{m}$$

$$L_0 = W_0 \cdot \frac{R_0}{R_{square}} = 4.2\mu\text{m} \cdot \frac{10000}{100} = 420\mu\text{m}$$

b. $C_{parasitic} = \frac{W_0 L_0 \epsilon_{ox}}{t_{ox}} = 61\text{fF}$

$$f_{limit} = \frac{1}{2\pi \cdot R_0 \cdot C_{parasitic}} = \frac{1}{2\pi \cdot 10 \cdot 10^3 \cdot 61 \cdot 10^{-15}} = 260\text{MHz}$$

The higher the accuracy required, the wider the resistor and the lower the frequency limit.